	Hits	Search Text	DBs
17	46	form\$3) same (selective\$3 or	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
18	7	<pre>(mask\$3 same opening))) and ((heat\$4 or anneal\$7 or bak\$4)</pre>	
19	160	((heat\$4 or anneal\$7 or bak\$4) near8 simultaneous\$3 near9 (strip\$5 or remov\$4 or etch\$4 or detach\$5) near9 (mask or pattern	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
20		((heat\$4 or anneal\$7 or bak\$4) near8 simultaneous\$3 near9 (strip\$5 or remov\$4) near9 (mask or pattern or photoresist or resist))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
21	31	((heat\$4 or anneal\$7 or bak\$4 or cur\$4) near14 simultaneous\$3 near12 (strip\$5 or remov\$4) near14 (mask or pattern) near9 (photoresist or resist or polylmer\$3))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
22	85	((pyrolysis or pyr\$1oly\$4 or sublimat\$5) near16 (mask or pattern) near9 (photoresist or resist))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB